

High-Index Fluoride Single Crystal for 193 nm Immersion Lithography

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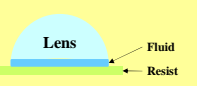
Motivation

High Refractive Index Material (HIM) is required for Hyper-NA 193nm Immersion Lithography in 2 Years!

$$\text{Resolution} = k_1 (\text{factor}) \times (193\text{nm}) / \text{NA}$$

$$\text{NA} = n \times \sin \theta \quad \text{where } n: \text{refractive index}$$

'n' is restricted by minimum ($n_{\text{lens}}, n_{\text{fluid}}, n_{\text{resist}}$)

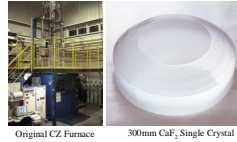


Candidates for HIM (our impression)

	Refractive Index	IBR	Melting Point [°C]	Size (Thickness)	Transmittance / Laser Durability
Oxide crystals	High	poor	1900-	middle	poor
Oxide ceramics	High	good	-	poor	poor
Fluoride crystals	Low-Middle	middle	800-1400	good	good?

Concept of Tokuyama

- Core Technology
 - Czochralski Method
 - Large Diameter
 - Fluoride Single Crystal



Goal

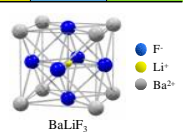
- Develop High Index Fluoride Single Crystal
BaLiF₃ (n₁₉₃=1.64) 150 x > t50 <100
- Develop Large Diameter <100> CaF₂ for IBR Compensation
CaF₂ 300 x > t50 <100

Basic Property of BaLiF₃

	CaF ₂	LiF	BaF ₂	BaLiF ₃
Crystal structure	cubic	cubic	cubic	cubic
Lattice constant [Å]	5.462	4.028	6.196	3.995
Melting point [°C]	1460	870	1355	880
Density [g/cm ³]	3.18	2.64	4.89	5.28
Refractive Index @ 193nm	1.50	1.44	1.58	1.64
IBR @ 193nm [nm/cm]	-3.4	n.a.	19.0	25.4

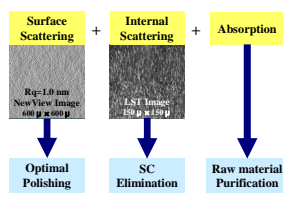
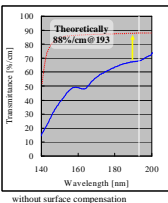


BaLiF₃ <100> 120 x t100



Critical Issue of BaLiF₃ as of SPIE2006

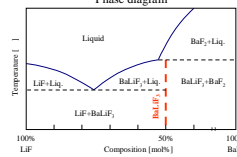
	Orient-ation	Refractive Index	IBR [nm/cm]	dn/dt	A ₁₀ [1/cm]	SBR [nm/cm]	HG(-Z36) [ppb]	Size [mm]
Target	<100>	>1.7	<10	<2.3 × 10 ⁻⁵	<0.01	<1	n.a.	150 x t50
BaLiF ₃	<100>	1.64	+25.4	-2.3 × 10 ⁻⁵	-0.13	0.6	n.a.	120 x t100
CaF ₂	<100>	1.50	-3.4	-2.9 × 10 ⁻⁵	0.0005	0.6	20-40	250 x t50



Results of Crystal Growth by CZ method

BaLiF₃ melts incongruently! It can not be grown from stoichiometric melt composition.

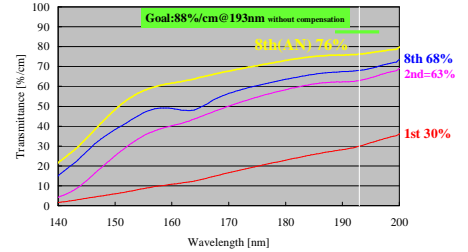
Melt comp. Li:Ba	Obtained crystal
50:50	Never eutectic
53:47	Partial eutectic
55:45	Relatively clear
57:43	Milky-Clear



Growth Condition	1.0	2.0
Pulling speed [mm/hr]	1.0	0.5
Cooling rate [hr]	60	4

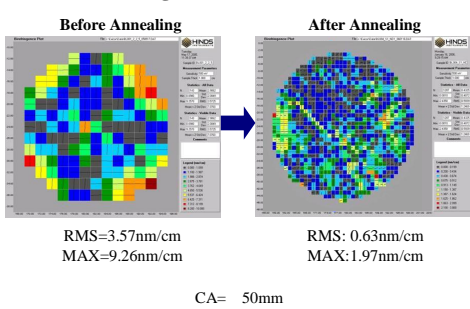
Results
Melt composition : Li Rich
Pulling speed: Slow
Cooling rate: Fast

Result of Diffusive Annealing

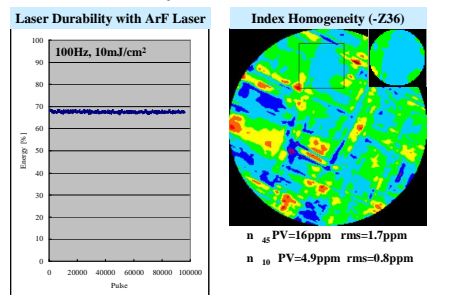


Result
Transmittance was improved by annealing process!

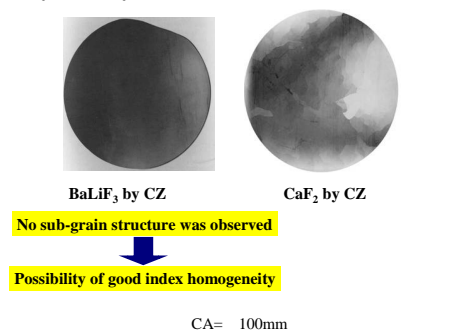
Stress Birefringence at 633nm



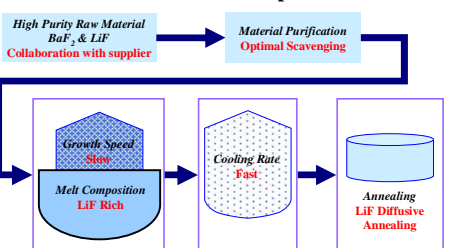
Some Preliminary Results



Crystallinity



Development Concept for Transmittance Improvement



Optical Property Up-date & Schedule

	Orient-ation	Refractive Index	IBR [nm/cm]	dn/dt	A ₁₀ [1/cm]	SBR [nm/cm]	HG(-Z36) [ppm]	Size [mm]
BaLiF ₃	(100)	1.64	+25.4	-2.3 × 10 ⁻⁵	0.067	0.6	-1	120 x t100

Schedule	2005			2006											
	9	10	11	1	2	3	4	5	6	7	8	9	10	11	12
Diameter	50			120 → 150 → 190 → 250											
Quality Improvement	VUV			Laser Durability, SBR, Homogeneity, Sample Shipment											
Phase	Phase-1 R&D → Phase-2														

Conclusion

- Tokuyama try to manufacture BaLiF₃ as HIM and large <100> CaF₂ for IBR compensation.
- Critical issue of BaLiF₃ is transmittance. Champion: 0.067 [1/cm] / 85 [%/cm] *Compensated data
- Cause of transmittance debasement might be mainly due to scattering of LiF precipitation.
- Transmittance could be improved by way of optimal growth condition and special annealing process.
- Tokuyama will try to improve transmittance and assess possibility of BaLiF₃ by the end of September.